



Specification

1.01262.0000 Water Ultrapur

	Specification		Method
Ag (Silver)	≤ 50	ppt	ICP-MS
Al (Aluminium)	≤ 200	ppt	ICP-MS
As (Arsenic)	≤ 50	ppt	ICP-MS
Au (Gold)	≤ 50	ppt	ICP-MS
B (Boron)	≤ 500	ppt	ICP-MS
Ba (Barium)	≤ 50	ppt	ICP-MS
Be (Beryllium)	≤ 50	ppt	ICP-MS
Bi (Bismuth)	≤ 50	ppt	ICP-MS
Ca (Calcium)	≤ 500	ppt	ICP-MS
Cd (Cadmium)	≤ 50	ppt	ICP-MS
Ce (Cerium)	≤ 20.0	ppt	ICP-MS
Co (Cobalt)	≤ 50	ppt	ICP-MS
Cr (Chromium)	≤ 50	ppt	ICP-MS
Cu (Copper)	≤ 100	ppt	ICP-MS
Dy (Dysprosium)	≤ 20.0	ppt	ICP-MS
Er (Erbium)	≤ 20.0	ppt	ICP-MS
Eu (Europium)	≤ 20.0	ppt	ICP-MS
Fe (Iron)	≤ 300	ppt	ICP-MS
Ga (Gallium)	≤ 50.0	ppt	ICP-MS
Gd (Gadolinium)	≤ 20.0	ppt	ICP-MS
Ge (Germanium)	≤ 50	ppt	ICP-MS
Hf (Hafnium)	≤ 10.0	ppt	ICP-MS
Ho (Holmium)	≤ 20.0	ppt	ICP-MS
In (Indium)	≤ 50.0	ppt	ICP-MS
K (Potassium)	≤ 300	ppt	ICP-MS
La (Lanthanum)	≤ 20.0	ppt	ICP-MS
Li (Lithium)	≤ 50.0	ppt	ICP-MS
Lu (Lutetium)	≤ 20.0	ppt	ICP-MS
Mg (Magnesium)	≤ 100	ppt	ICP-MS
Mn (Manganese)	≤ 50	ppt	ICP-MS
Mo (Molybdenum)	≤ 50	ppt	ICP-MS
Na (Sodium)	≤ 500	ppt	ICP-MS
Nb (Niobium)	≤ 20.0	ppt	ICP-MS
Nd (Neodymium)	≤ 20.0	ppt	ICP-MS
Ni (Nickel)	≤ 50	ppt	ICP-MS
Pb (Lead)	≤ 50	ppt	ICP-MS
Pd (Palladium)	≤ 50	ppt	ICP-MS
Pr (Praseodym)	≤ 20.0	ppt	ICP-MS
Pt (Platinum)	≤ 50	ppt	ICP-MS
Rb (Rubidium)	≤ 20.0	ppt	ICP-MS
Sb (Antimony)	≤ 50	ppt	ICP-MS

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Sc (Scandium)	≤ 20	ppt	ICP-MS
Si (Silicon)	≤ 1000	ppt	GFAAS
Sm (Samarium)	≤ 20.0	ppt	ICP-MS
Sn (Tin)	≤ 50	ppt	ICP-MS
Sr (Strontium)	≤ 50.0	ppt	ICP-MS
Ta (Tantalum)	≤ 50.0	ppt	ICP-MS
Tb (Terbium)	≤ 20.0	ppt	ICP-MS
Te (Tellur)	≤ 50	ppt	ICP-MS
Th (Thorium)	≤ 10.00	ppt	ICP-MS
Ti (Titanium)	≤ 50	ppt	ICP-MS
Tl (Thallium)	≤ 50.0	ppt	ICP-MS
Tm (Thulium)	≤ 20.0	ppt	ICP-MS
U (Uranium)	≤ 10.00	ppt	ICP-MS
V (Vanadium)	≤ 50	ppt	ICP-MS
W (Wolfram)	≤ 100	ppt	ICP-MS
Y (Yttrium)	≤ 10.0	ppt	ICP-MS
Yb (Ytterbium)	≤ 20.0	ppt	ICP-MS
Zn (Zinc)	≤ 500	ppt	ICP-MS
Zr (Zirconium)	≤ 50.0	ppt	ICP-MS

ICP-MS: Determination after evaporation to dryness with ICP-MS

GFAAS: Determination after preconcentration with graphite furnace AAS

Actual analysis values are subject to unavoidable systematic variations in this concentration range.

Evelyn Allmann

Responsible laboratory manager quality control

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